Plenary Speaker James Gibbons **Considers "Lessons from** Silicon Valley"

James F. Gibbons of Stanford University will consider "Lessons from the History of Silicon Valley: Start-Ups and Strategic Alliances" in his plenary presentation at the 1994 MRS Spring Meeting in San Francisco. The Plenary Session is scheduled for Monday, April 4 at 6 p.m. and will

be followed by a reception.

Gibbons is the Frederick Emmons Terman Dean of Stanford's School of Engineering. He also serves on the U.S.-Japan Joint High Level Advisory Panel and on the National Research Council Committee on Science, Technology and Economic Policy. He has an extensive background in semiconductor electronics and maintains a strong interest in engineering education.

Gibbons' principal research interests are in semiconductor device analysis, process physics and technology, and solar energy. He has been the author or co-author of four textbooks in semiconductor electronics and of four research monographs on ion implantation and beam processing of semi-

conductors.

In 1972, Gibbons devised a Tutored Video Instruction technique. He and colleagues at Stanford and Hewlett-Packard have since developed the technique into a highly regarded model for in-plant education of engineers. He is currently involved with using the technique to improve educational productivity and quality at all levels, including basic education for juvenile offenders and the children of migrant farm workers and in-service teacher training for K-6 science and mathematics teachers.

Gibbons was educated at Northwestern University and Stanford University, and did postdoctoral research at Cambridge University, England. He joined the

Stanford faculty in 1954.

He has consulted widely in the semiconductor electronics industry. He has served several agencies of the U.S. government and has participated on panels reporting to the President's Science Advisor during the Nixon, Reagan, and Bush administrations. In the international arena, he was a member of the U.S. scientific team for international scientific exchanges on ion implantation and beam processing to Japan, China, the former Soviet Union, and Australia.

Gibbons is a Fellow of IEEE and the recipient of several IEEE awards. He is a member of the U.S. National Academy of Engineering and the National Academy of Science, the Royal Swedish Academy of Engineering Science, and the Norwegian Academy of Technical Science. MRS

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